

AMENDMENTS TO THE CLAIMS

Claim 1 (Cancelled)

Claim 2 (Cancelled)

Claim 3 (Cancelled)

Claim 4 (Cancelled)

Claim 5 (Currently Amended) A dry etching method comprising etching a metallic surface of copper, silver, gold, or an alloy containing as a main component at least one of these metals by plasma of an etching gas containing a gaseous nitrogen oxide, hydrogen sulfide and ammonia while being reacted with the plasma.

Claim 6 (Cancelled)

Claim 7 (Cancelled)

Claim 8 (Currently Amended) A dry etching method as claimed in Claim 5, wherein a mask material selected from the group consisting of titanium and a titanium alloy covers the metallic surface on etching.

Claim 9 (New) A dry etching method comprising etching a metallic surface of copper, silver, gold, or an alloy containing as a main component at least one of these metals by plasma of an etching gas containing a gaseous nitrogen oxide and ammonia while being reacted with the plasma, wherein a mask material selected from the group consisting of titanium and a titanium alloy covers the metallic surface on etching.

Claim 10 (New) A dry etching method as claimed in Claim 9, wherein the etching gas further contains hydrogen sulfide.